

Eximor® SV1 Filter

Advanced disposable POU filters for critical photo-solvent applications

Eximor® SV1 filters provide the ultimate particle retention with rapid flush-up in sub 30 nm technology wafer processing applications.

Using the most advanced membrane technologies, Eximor SV1 filters are specially designed for use on Tokyo Electron Limited (TEL®) tracks in various reducing resist consumption (RRC) applications. The specially designed ultra-high molecular weight polyethylene (UPE) based membrane thickness offers sieving and non-sieving retention technologies that remove various contaminants and tiny particulate. The result is the cleanest point-of-use (POU) solution available with significantly lower on-wafer defects that ensures higher production yields.

Rapid Start-Up and Device Purity

Eximor SV1 filters use our unique Impact® 8G core-fill design for rapid priming that improves bubble clearance times. This priming time is further improved by an advanced cleaning procedure designed specifically for solvents used in the targeted applications. This leads to even lower non-volatile residue (NVR) and metals extractables and ensures a flush-up time that is superior to other POU filters.

APPLICATIONS

- RRC solvents



Designed for TEL tracks in RRC solvent applications.

FEATURES & BENEFITS

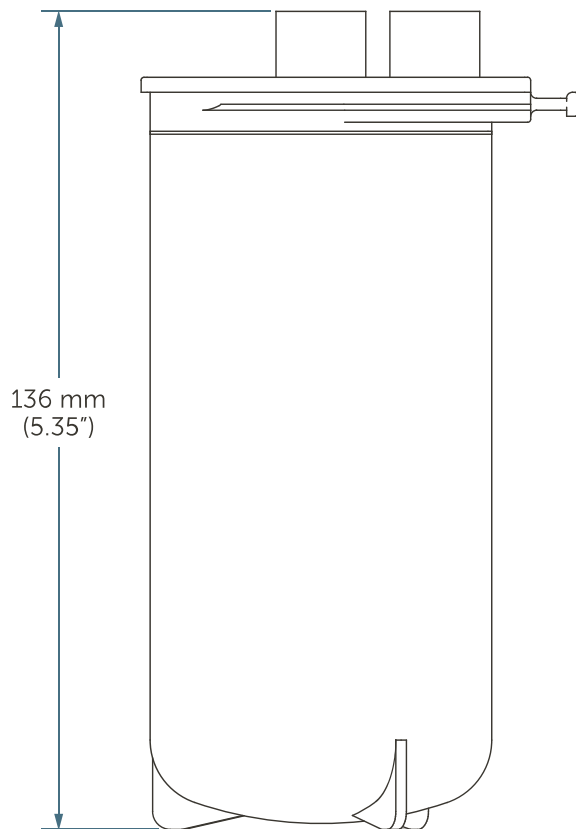
Jointly developed with TEL	Ensures filter priming by dedicated TEL priming recipe
	Provides optimized performance for TEL track priming system
Core fill structure	Reduces overall filter priming time leading to reduced filter start-up costs
	Efficient priming promotes a rapid, stable, repeatable environment with lower defectivity
Specially designed PE-based membrane technology	Reduces on-wafer defects in sub 30 nm technology wafer processing
	Ensures tight retention and low pressure drop performance
	Additional non-sieving retention further reduces particles and ensures the cleanest on-wafer solvents possible at start up

SPECIFICATIONS

Materials	Membrane	UPE
	Shell, core, supports	High-density polyethylene (HDPE)
	O-ring (OF)	Kalrez® perfluoroelastomer
Maximum operating conditions	Maximum inlet pressure	0.34 MPa (3.4 bar, 50 psi) @ 25°C (77°F)
	Maximum forward/reverse differential pressure	0.27 MPa (2.7 bar, 39 psi) @ 25°C (77°F)
	Maximum operating temperature	40°C (104°F)
Compatibility	Propylene glycol methyl ether acetate (PGMEA), propylene glycol monomethyl ether (PGME), any other solvents (contact your local Entegris applications engineer for details)	
Hold up volume	110 cc	
Typical flow rate	250 cc/min (20°C, 1 mPa•s) with 0.03 MPa pressure drop	

Entegris recommends that customers change filters at least annually to ensure optimal filtration performance. Routine annual changeout will also reduce the potential of chemical leakage that can result from excessive usage. Our standard warranty period is 1 year (from Entegris ship date).

DIMENSIONS



ORDERING INFORMATION

PART NUMBER	PRODUCT TYPE
EX1KCL0K1	Eximor SV1 disposable filter

FOR MORE INFORMATION

Please call your Regional Customer Service Center today to learn what Entegris can do for you. Visit entegris.com and select the [Contact Us](#) link to find the customer service center nearest you.

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